

## JM<sup>3</sup> is Gone, Long Live JM<sup>3</sup>!

**Harry Levinson and Hans Zappe**  
JM<sup>3</sup> Co-Editors-in-Chief



**Levinson**



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After 14 years, we have come to the last issue of the *Journal of Micro/Nanolithography, MEMS and MOEMS*, established in the lithography and MEMS communities as JM<sup>3</sup>. Yet JM<sup>3</sup> lives on: starting next year, the acronym will refer to the *Journal of Micro/Nanopatterning, Materials, and Metrology*, an SPIE journal dedicated wholly to lithography and patterning.

Our MOEMS authors and readers will have a new journal home, as the *Journal of Optical Microsystems* (JOM) will launch in 2021. With a focus on micro-optical technologies, photonic devices, and optical systems applications, this newest addition to the SPIE journal portfolio will address both academic and industrial readers, anyone working on small-scale optical systems. Alas, there will no longer be a niche for non-optical MEMS research, as we saw in the past few years that this area has too small a profile within the focus on optics of journals published by SPIE.

As co-editors-in-chief of JM<sup>3</sup> for 2020, we will now continue with our editorial adventures on separate paths after a year of exceedingly fruitful and very productive collaboration. Several members of the JM<sup>3</sup> editorial board have joined JOM, with the remaining senior editors and associate editors continuing to support JM<sup>3</sup>. Going forward, both journals, JOM and the new JM<sup>3</sup>, will profit from continuity in our hard-working team of editors.

Our aim is that the new JM<sup>3</sup> and JOM will now grow to become key journals in our fields and it is on you, our dedicated authors and faithful readers, that we will rely on to make that happen. We thank you for 14 years of steadfast contributions and committed readership and look forward to decades more with our two new publications.